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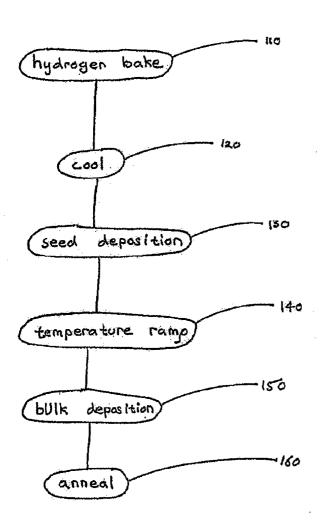
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(54) Title: GERMANIUM DEPOSITION



(57) Abstract: A method comprises, depositing a seed layer of germanium over a silicon-containing surface at a first temperature in a seed deposition process 130. The seed layer has a thickness between about one monolayer and about 1000 Å. The method further comprises, after depositing the seed layer, increasing the temperature of the reaction chamber while continuing to deposit germanium in a temperature ramp process 140. The method further comprises holding the reaction chamber in a second temperature range while continuing to deposit germanium in a bulk deposition process 150. The second temperature range is greater than the first temperature.

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ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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IPC:	C30B 25/16(2006.01),29/08(2006.01);C23C 16/22	(2006.01),16/52(2006.01);H01L 21/205((2006.01)				
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B. FIELDS SEARCHED							
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	cumentation searched (classification system followed by 7/89,105,936;427/255.35;438/478,493,505,508,933,93		·				
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C. DOC	UMENTS CONSIDERED TO BE RELEVANT						
Category *	Citation of document, with indication, where ap	propriate, of the relevant passages	Relevant to claim No.				
X, T	US 2005/0067377 A1 (Lei et al.) 31 March 2005 (31.	03.2005), Para. [0015]	1, 5, 7				
 Ү, Т			4				
Y, P X Y	US 2004/0092104 A1 (Gunn III, et al.) 13 May 2004 [0019], [0021], [0026], [0028], [0036]. US 6,537,370 B1 (Hernandez et al.) 25 March 2003 (column 7, lines 1-15; column 8, lines 37-43; column	25.03.2003), column 6, lines 53-54;	2, 3, 7-10, 23-25, 27, 65-67 1, 4-6, 28, 35, 36, 39, 42, 43, 46-51, 59, 62, 63 				
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	documents are listed in the continuation of Box C.	See patent family annex.	1.00				
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"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)		'Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being					
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INTERNATIONAL SEARCH REPORT

ategory *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.	
Y	Luan et al., High quality Ge epilayers on Si with low threading dislocation densities, Applied Physics Letters, Volume 75, Number 19, 8 November 1999, pages 2090-2911, especially Table 1, Figure 1and pages 2909-2911.	31, 32, 40, 41, 44, 45 52, 53	
Α	6,635,110 B1 (Luan et al.) 21 October 2003 (21.10.2003).	1-67	
Α	6,429,098 B1 (Bensahel et al.) 06 August 2002 (06.08.2002).	1-67	
Α	6,107,653 A (Fitzgerald) 22 August 2000 (22.08.2000).	1-67	
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